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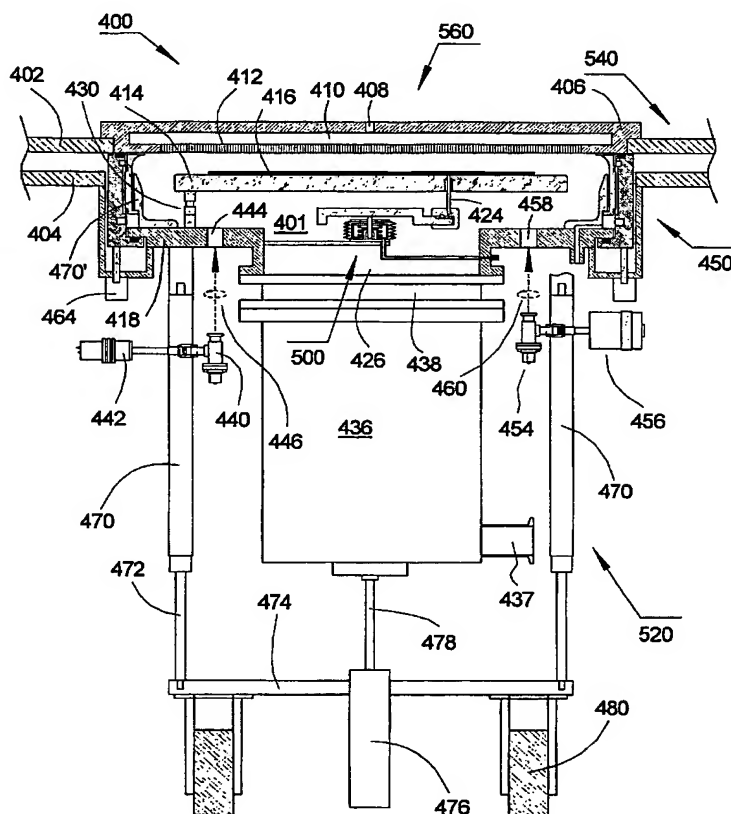
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60/501,943 11 September 2003 (11.09.2003) US
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- (74) Agents: FOREST, Carl, A. et al.; Patton Boggs LLP, 1660
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- (81) Designated States (unless otherwise indicated, for every
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(54) Title: PERIMETER PARTITION-VALVE WITH PROTECTED SEALS AND ASSOCIATED SMALL SIZE PROCESS CHAMBERS AND MULTIPLE CHAMBER SYSTEMS



(57) Abstract: A seal-protected perimeter partition valve apparatus (450) defines a vacuum and pressure sealed space (401) within a larger space (540) confining a substrate processing chamber with optimized geometry, minimized footprint and 360° substrate accessibility. A compact perimeter partitioned assembly (520) with seal protected perimeter partition valve (450) and internally contained substrate placement member (480) further provides processing system modularity and substantially minimized system footprint.

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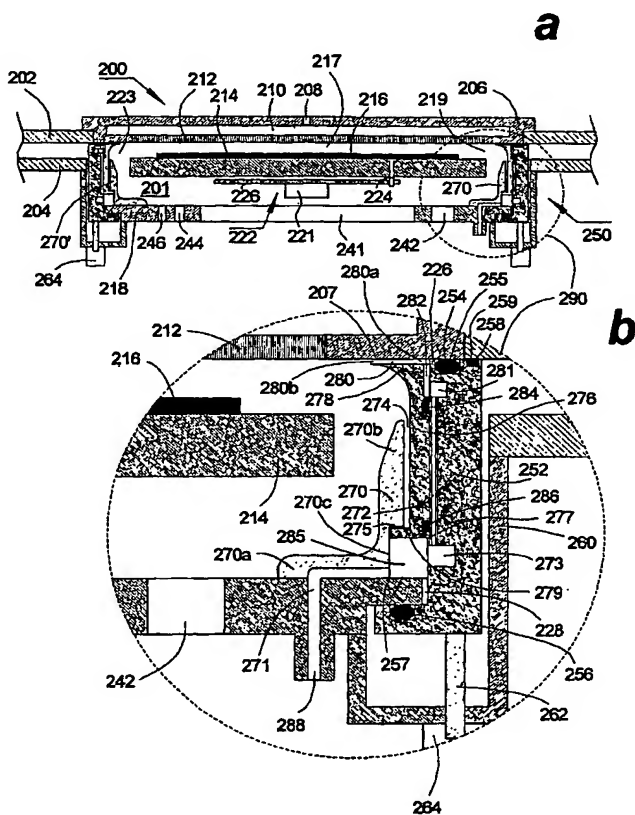
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